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ON THE KINETICS OF BORON NITRIDE CVD FROM BF3-NH3-Ar:

2 - INFLUENCE OF THE PRECURSOR COMPOSITION AND CHEMICAL MECHANISMS.

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#### ABSTRACT

An experimental study is used to assess the kinetics of boron nitride CVD from  $BF_3$ - $NH_3$ -Ar mixtures and the influence of the initial gas phase composition on the transition from mass transfer to chemical reaction rate-controlled processes. The extension of the chemical reaction rate-controlled domain in the coordinates  $P_{BF_3}$ - $P_{NH_3}$  is determined for three temperatures (1250, 1350 and 1450 K) and a given total flow rate ( $Q_{tot}$ = 119 sccm). In the surface reaction controlled regime, the kinetic laws are established; apparent partial reaction orders with respect to  $BF_3$ ,  $NH_3$ , Ar and HF are given for various conditions. The apparent partial reaction orders with respect to Ar and Ar are nil and those with respect to Ar and Ar are nil and those with respect to Ar and Ar are nil and total pressure. Finally, reactional mechanisms, according to the kinetic laws and chemical analyses performed on deposits obtained in the

domains corresponding to these laws, are proposed to explain the chemical processes of BN deposition. One mechanism assumes the occurrence of the  $BF_3:NH_3$  adduct in the gas phase at low temperatures; the other, at higher temperatures, is based on the hypothesis that  $NH_3$  is preferentially adsorbed on the substrate and reacts with the  $BF_3$  present in the gas phase.

**KEY WORDS**: Boron Nitride, CVD, Kinetics, BF<sub>3</sub>, NH<sub>3</sub>, Reactionnal mechanisms

## 1-INTRODUCTION

Chemically vapour deposited boron nitride exhibits very interesting physical and chemical properties which are known to highly depend on the conditions of synthesis (i. e. electrical properties and sensivity to the moisture [1]).

Whatever the gas mixture used as precursor of BN, the change of the experimental parameters (i. e. pressure, temperature and total flow rate) induces important variations in density, morphology, structure of the deposits and stablity to moisture [2-8]. Moreover, the oxygen plays an important catalytic role in the "graphitization process" of turbostratic boron nitride [9]. The influence of the initial gas phase composition on the nature of the deposit was approached in previous studies [3,4,10] that described the variation of morphology and growth rate as a function of the ratio NH<sub>3</sub>/BCl<sub>3</sub>.

The companion article (part 1) [11] detailed the influence of the main CVD parameters on the BN deposition kinetics, in the BF<sub>3</sub>-NH<sub>3</sub>-Ar system. Moreover, the initial composition of the gaseous precursor defined by the  $\alpha$  ratio of the partial pressures of NH<sub>3</sub> and BF3:  $\alpha = P_{\rm NH_3}/\,P_{\rm BF_3}$  seemed to be a

critical parameter. Indeed, the extension of the chemically controlled deposition domain was found to be very different for two distinct  $\alpha$  values.

The purpose of the present contribution is: (i) to study more precisely the influence of the α-parameter on the transition from mass transfer to chemical reaction rate controlled processes and on the chemical composition of the deposit and(ii) to determine, in the different thermally activated domains, the kinetic laws and to propose an approach of the chemical mechanisms.

## 2-RESULTS

# 2.1- Influence of the initial gas phase composition on the transition between physical and chemical rate control.

The influence of the initial composition of the gas phase upon the transition between the diffusion-controlled and the reaction-controlled regimes is studied following the method developed in part 1 [11]. The experiments were performed by using the previously described apparatus for three temperatures (1250, 1350 and 1450 K) with an  $\alpha$  ratio ranging from 0.5 to 5, the dilution ratio  $\beta$  ( $\beta$ =  $P_{Ar}$ /  $P_{NH_3}$ + $P_{BF_3}$ ) and the total flow rate ( $Q_{tot}$ =110-120 sccm) being maintained constant.

Under these conditions, the variations of the growth rate, as a function of the total reactive pressure (defined as  $P_{tr} = P_{NH_3} + P_{BF_3}$ ), and the corresponding total pressure ( $P = P_{Ar} + P_{tr} = (1+\beta) P_{tr}$ ) are shown in figures 1 to 3. For the three temperatures, the curves exhibit two distinct parts. At low pressures, the growth rate increases with  $P_{tr}$  and then remains rather constant or slightly decreases. A transition pressure range, located around the maximum of growth rate-total reactive pressure curve, is defined for each  $\alpha$ 

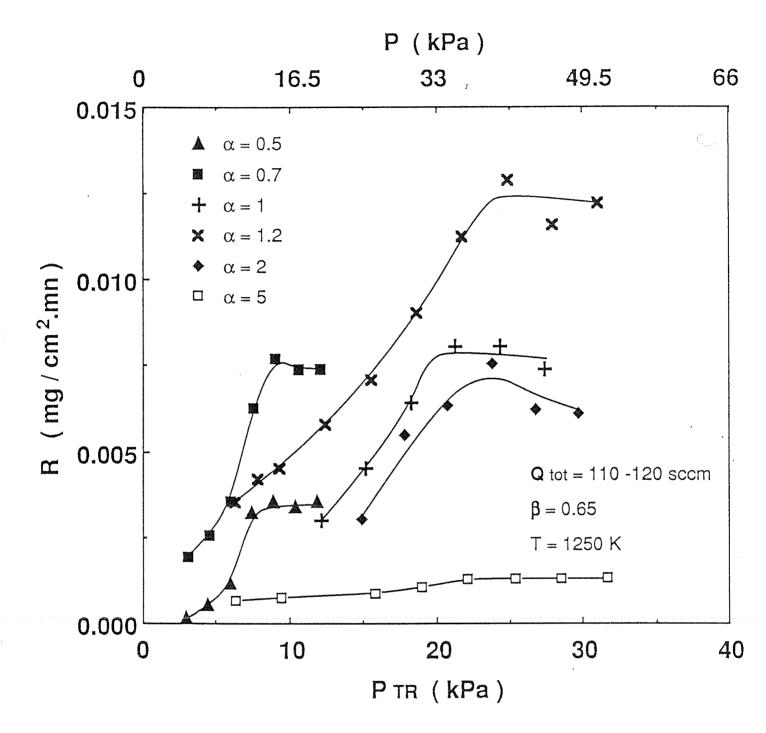


Fig.1: Variations of BN growth rate with total pressure P and total reactive pressure Ptr for T= 1250 K and various α values

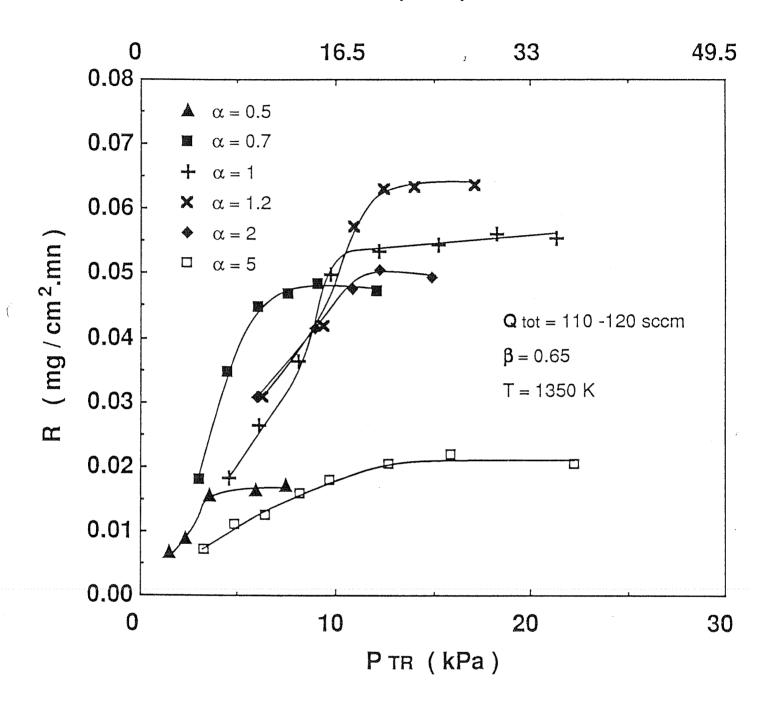


Fig.2 : Variations of BN growth rate with total pressure P and total reactive pressure  $P_{tr}$  for T=1350 K and various  $\alpha$  values

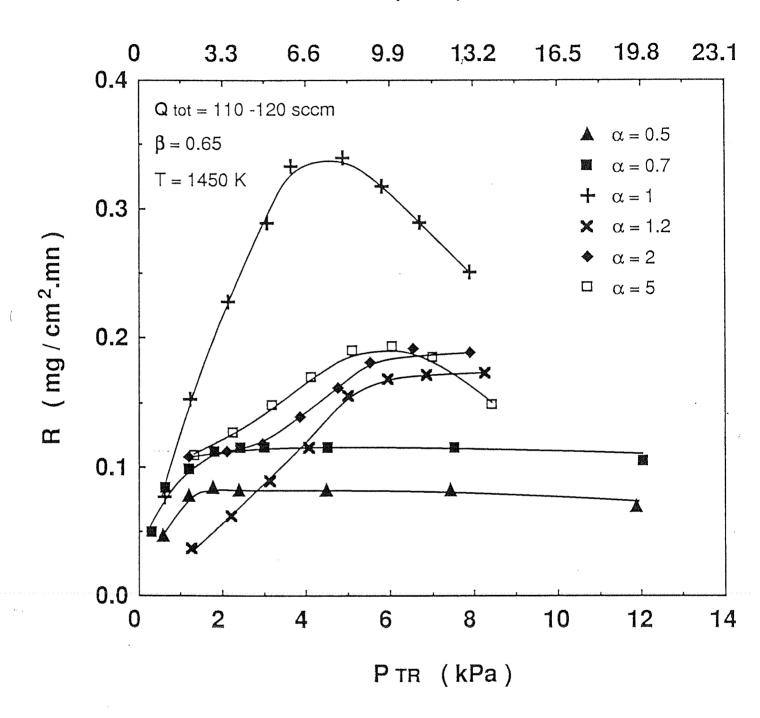


Fig.3 : Variations of BN growth rate with total pressure P and total reactive pressure  $P_{tr}$  for T=1450 K and various  $\alpha$  values

ratio at a given temperature, total flow rate and dilution ratio. The  $(\alpha, P_{tr})$  couples are then plotted in the plane  $(P_{BF_3}, P_{NH_3})$ . The interest of such a representation mode is detailed in appendix. The plots established for T=1250 K (Fig. 4) define the limit between two domains. In the low pressures domain, the deposition rate is limited by chemical reaction kinetics. For higher total reactive pressures, mass transfers become the limiting phenomena of the deposition process. Total reactive pressure values which induce the transition between these two regimes are constant for  $\alpha \geq 1$ . For  $\alpha \leq 1$ , the transition pressure decreases with  $\alpha$ . The chemical rate-controlled domain is narrowed when  $BF_3$  becomes the major species in the initial gaseous phase.

As the temperature is increased, the extension of the reaction-controlled domain decreases but exhibits the same shape, (Fig. 5). This is in accordance with the tendencies determined from the (P,T) plots in [11], and with the general trend in CVD processes which is to favor physical rate limitation by increasing temperature [10-13].

## 2.2- Apparent reaction orders

When the chemical reactions are the rate-controlling steps in the CVD process, it is of interest to assess experimental apparent reaction orders with respect to the reactant species (NH $_3$  and BF $_3$ ) introduced in the gas phase. The influences of HF (the main gas product) and Ar (used as dilution species) must be also studied in order to derive complete kinetic laws and to suggest chemical mechanisms for the deposition process. In the case of HF (the main reaction product), the added partial pressure is rather important with respect to total reactive pressure  $P_{tr}$ .

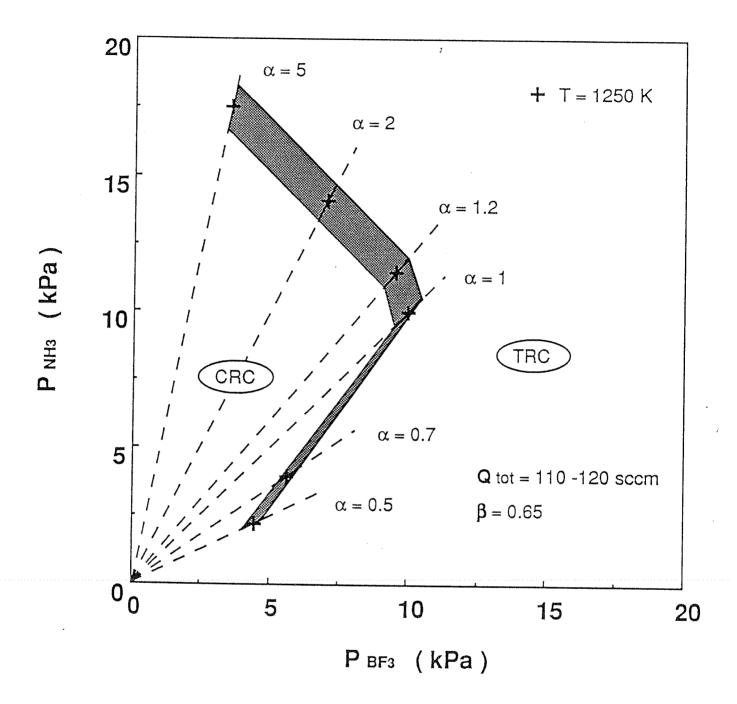


Fig.4: Transition zone in terms of PBF3 and PNH3 between transfer rate control (TRC) at high pressures and chemical rate control (CRC) at low pressures of the BN deposition process, for T= 1250 K and various compositions of the initial gaseous mixture

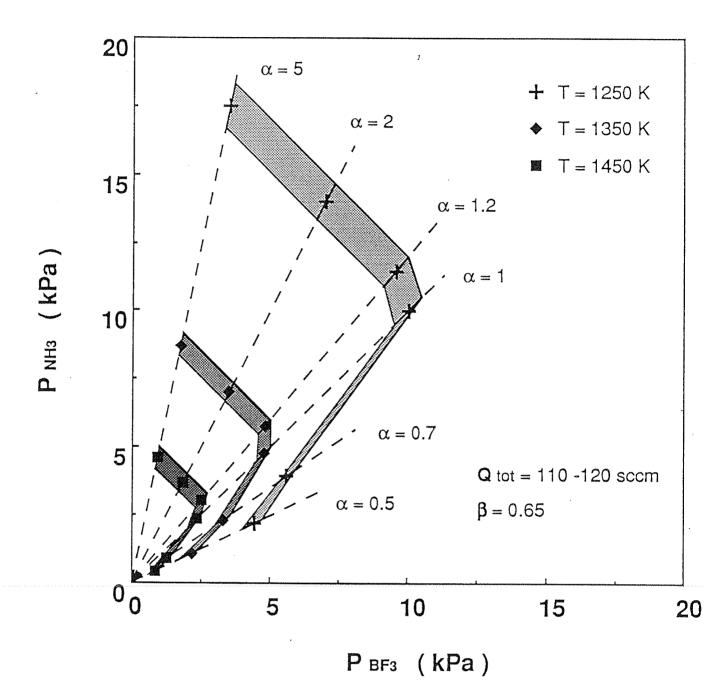


Fig.5: Transition zone in terms of PBF3 and PNH3 between transfer rate control (TRC) at high pressures and chemical rate control (CRC) at low pressures of the BN deposition process, for T= 1250, 1350 and 1450 K, and various compositions of the initial gaseous mixture

The influence of various partial pressures on the deposition rate of BN was quantitatively studied for three temperatures (1250,1350 and 1450 K) and conditions of total reactive pressure suitably defined according to the conclusions of the last section. In order to determine the apparent reaction order with respect to a species i, the experiments are performed by maintaining constant the flow rates Qj and the partial pressures  $P_j$  of all the species j (with  $j\neq i$ ) and by varying the total pressure and the partial flow rate and pressure of the considered species i. The data are shown in figures 6 to 19 as  $\ln R = f(\ln P_i)$  curves. These are found to be straight lines and for HF species the slope  $n_3$  is negative. In order to get a finite value for the growth rate R when  $P_{\rm HF}$  is very low, a kinetic law of the following kind can fit with the experimental results:

$$R = \frac{k'_0 \exp(-E'_a/\Re T) [P_{BF_3}]^{n_1} \cdot [P_{NH_3}]^{n_2} \cdot [P_{Ar}]^{n_4}}{1 + (k''_0 \exp(-E''_a/\Re T) [P_{HF}]^{-n_3})}$$

where R is the reaction rate (mg/mn.cm<sup>2</sup>),  $k'_0$  and  $k''_0$  the pre-exponential factors of the kinetic constants,  $E'_a$  and  $E''_a$  the apparent activation energies,  $\Re$  the perfect gas constant, T the temperature,  $P_i$  the partial pressure of the species i (with i=1 to 4) and  $n_i$  the apparent reaction orders with respect to the reactants (NH<sub>3</sub>, BF<sub>3</sub>), the product (HF) and the dilution species (Ar).

If  $k''_0 \exp{(-\ E''_a/\Re T)}\ [P_{HF}]^{-n_3} << 1$  (i. e.  $[P_{HF}]\approx 0$ ), this law could be written as :

$$R = k'_0 \exp{(- \, E'_a / \, \Re T)} \, [P_{BF_3} \,]^{n_1} \, . \, [P_{NH_3}]^{n_2} . \, \, [P_{Ar}]^{n_4}$$

On the contrary, when  $k''_0 \exp(-\mathcal{E}''_a/\Re T)[P_{HF}]^{-n_3} >> 1$ , the kinetic law becomes :

$$\begin{split} R &= k_0 \, \exp \, (\text{-} \, (E'_a \text{-} E''_a) / \, \Re T) \, [P_{BF_3} \,]^{n_1} \, . \, [P_{NH_3}]^{n_2} . \, [P_{HF}]^{n_3} . \, [P_{Ar}]^{n_4} \\ & \text{or} \\ \\ R &= k_0 \, \exp \, (\text{-} \, E_a / \, \Re T) \, [P_{BF_3} \,]^{n_1} \, . \, [P_{NH_3}]^{n_2} . \, [P_{HF}]^{n_3} . \, [P_{Ar}]^{n_4} \end{split}$$

where  $k_0$  is the pre-exponential factor of the kinetic constant, and  $E_a$ = $\mathcal{E'}_a$ - $\mathcal{E''}_a$  the apparent activation energy.

The plots  $\ln R = f (\ln P_{BF_3})$ , recorded for T=1450 K and shown in figure 6, exhibit an apparent reaction order  $n_1=1$ . This value is obtained for  $P_{BF_3}$  ranging from 0.5 to 2 kPa and two partial pressures of NH<sub>3</sub> (1.5 and 2 kPa). For NH<sub>3</sub>, the apparent reaction order  $n_2$  is derived from two different sets of experiments carried out for  $P_{BF_3}$  equal to 1 and 0.5 kPa. In both cases it is considered to be zero (Fig. 7).

Data concerning Ar and HF [0.6  $\leq$  P<sub>HF</sub> $\leq$  1.35 kPa] are shown in figures 8 and 9. As could be expected, the apparent reaction order with respect to argon derived from three different runs in the total pressure range (1-6 kPa), is observed to be zero (n<sub>4</sub> = 0). The significant negative value (n<sub>3</sub> = -3) of the apparent reaction order with respect to HF suggests the important rôle played by this species in the formation of BN.

As a result, the following kinetic law is proposed for T= 1450 K and the domain of partial pressures defined in figure 9 and 10:

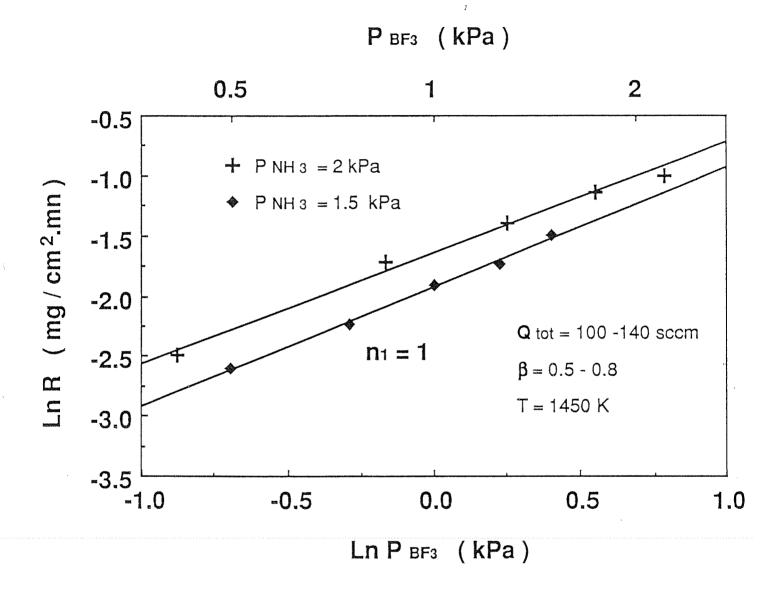


Fig.6: Variation of BN growth rate with partial pressure of BF3 for T= 1450 K

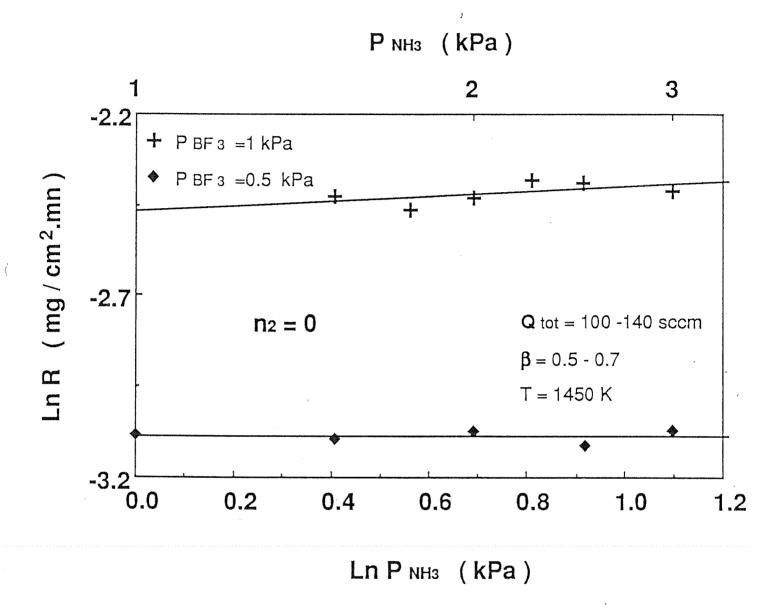


Fig.7: Variation of BN growth rate with partial pressure of NH3 for T= 1450 K

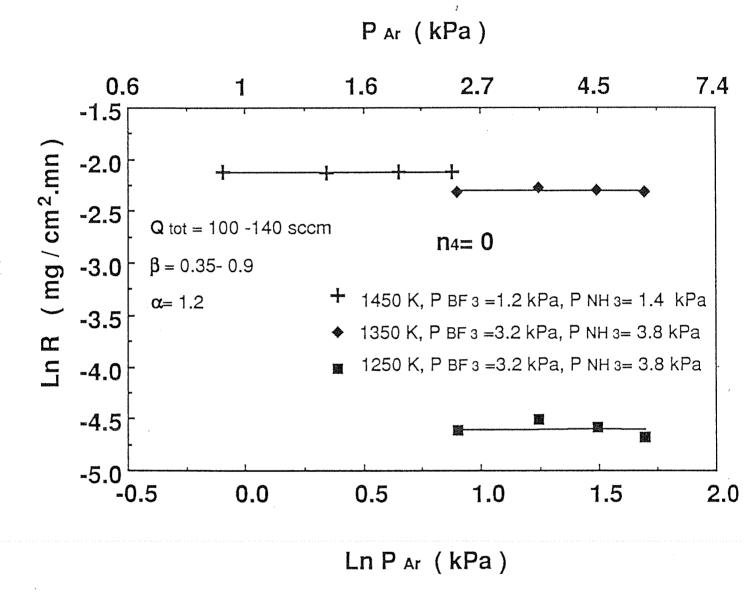


Fig.8: Variation of BN growth rate with partial pressure of Ar for different temperatures and total reactive pressures

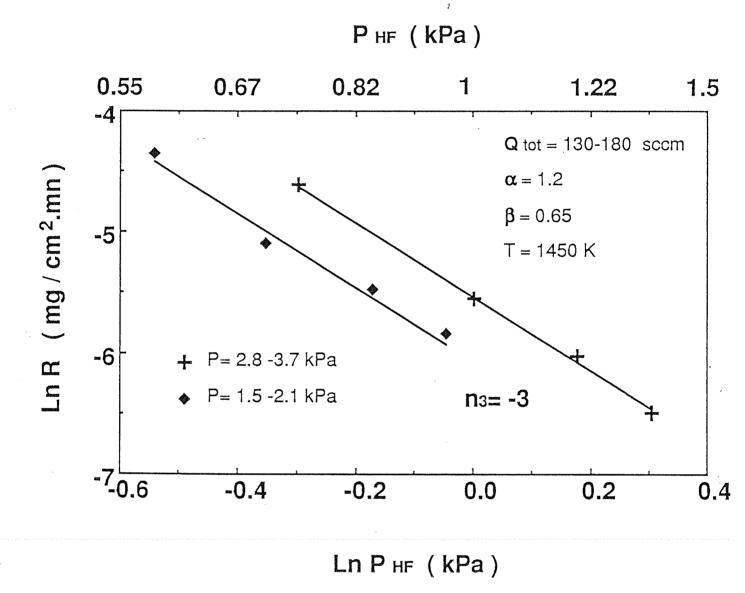


Fig.9: Variation of BN growth rate with partial pressure of HF for T= 1450

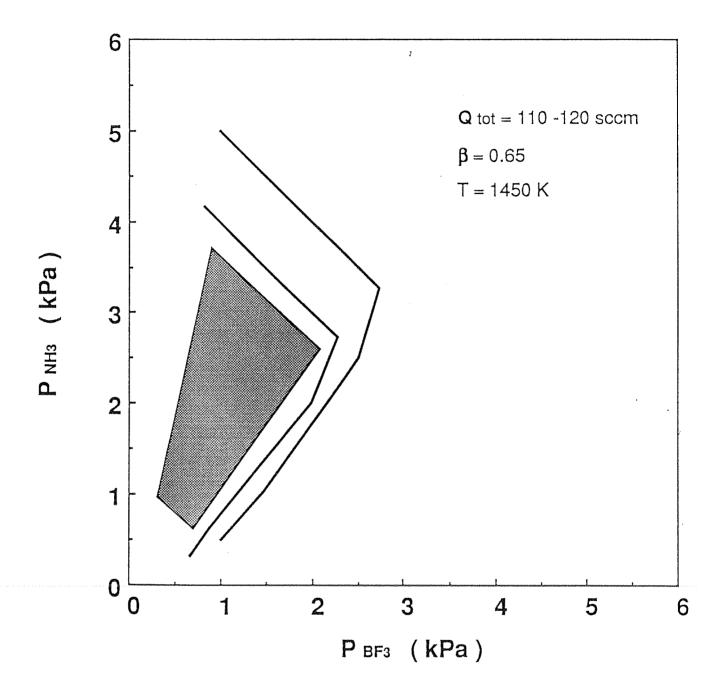


Fig.10 : Domain of validity for the kinetic law A at  $T=1450\ K$ 

$$\begin{split} R = k_0 \ exp \ (-E_a/RT) \ [P_{BF_3} \ ]^1. \ [P_{NH_3}]^0. \ [P_{HF}]^{-3}. \ [P_{Ar}]^0 \quad (Law \ A) \\ where \ E_a = 290 \pm 15 \ kJmol^{-1} \ [11], < k_0 > = 1.03.10 \ ^{14} \ mg.Pa^2/cm^2.mn \\ < k_0 > \text{is an average value calculated from all the experimental} \\ growth \ rates \ obtained \ in \ presence \ of \ added \ HF \ at \ 1450 \ K \end{split}$$

The data reported for T= 1350 K in figures 8, 11, 12, and 13, give the same partial orders with respect to all the species studied as in the preceding case.

The same kinetic law is proposed for a given domain of partial pressures of BF3 and NH3 (Fig. 14) and  $0.55 \le P_{HF} \le 1.4$  kPa:

 $R = k_0 \exp{(-E_A/\Re T)} [P_{BF_3}]^1. [P_{NH_3}]^0. [P_{HF}]^{-3}. [P_{Ar}]^0 \quad (Law \, A)$  where  $E_a = 290 \pm 15 \, kJmol^{-1} \, [11], < k_0 > = 6.5.10 \, ^{14} \, mg.Pa^2/cm^2.mn$  <  $k_0 >$  is an average value calculated from all the experimental growth rates obtained in presence of added HF for 1350 K

From the  $\ln R = f (\ln P_i)$  graphs established for T = 1250 K and shown in figures 8 and 15 to 19, it can be seen that the apparent reaction orders with respect to  $NH_3$  and argon are unchanged  $(n_2 = n_4 = 0)$ .

On the other hand, the influences of the partial pressures of BF<sub>3</sub> and HF on the deposition rate of BN are more complex. The data recorded from several runs, show the existence of two distinct partial reaction orders with respect to each species:

$$- n_1 = 0$$
 and  $n_3 = -1$ 

$$-n_1 = 1.5$$
 and  $n_3 = -2$ 

As a consequence, two different kinetic laws depending on the values of partial pressures of BF3 and NH3 (Fig. 20) are proposed:

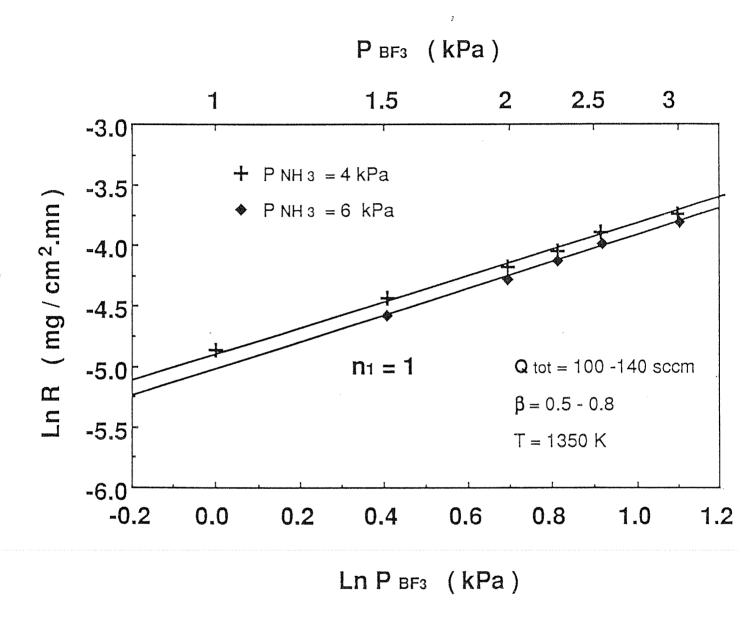


Fig.11: Variation of BN growth rate with partial pressure of BF3 for T= 1350 K

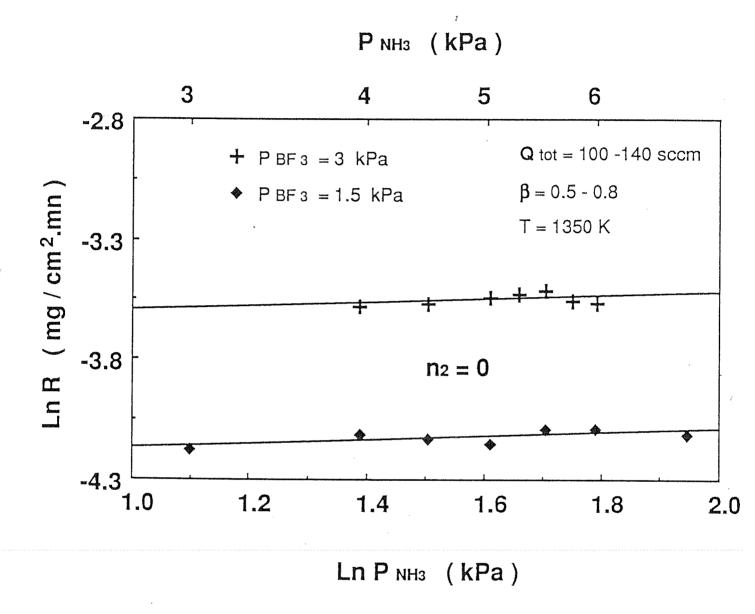


Fig.12: Variation of BN growth rate with partial pressure of NH<sub>3</sub> for T= 1350 K

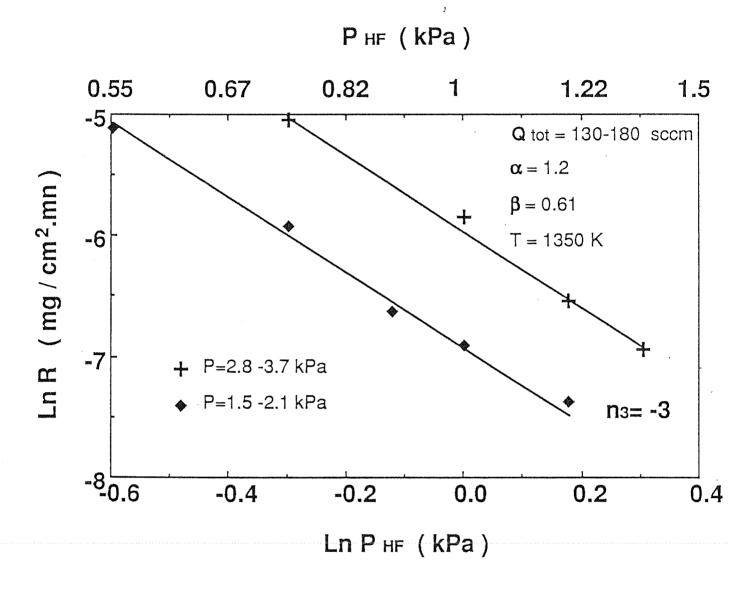


Fig.13: Variation of BN growth rate with partial pressure of HF for T= 1350 K

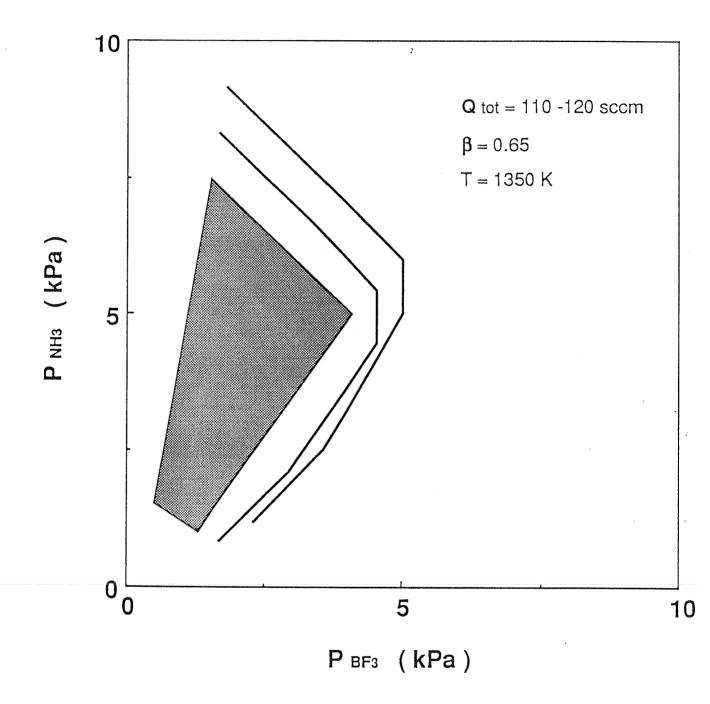


Fig.14 : Domain of validity for the kinetic law A at  $T=1350~\mathrm{K}$ 

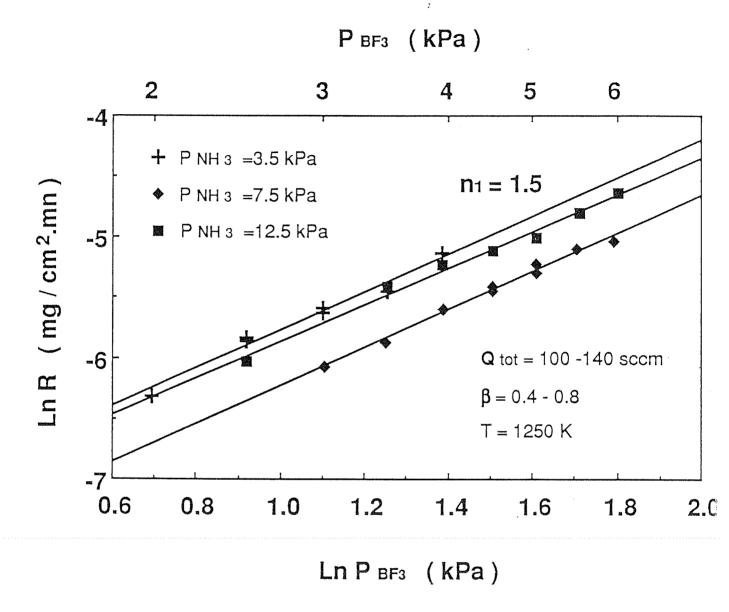


Fig.15: Variation of BN growth rate with partial pressure of BF3 for T= 1250 K

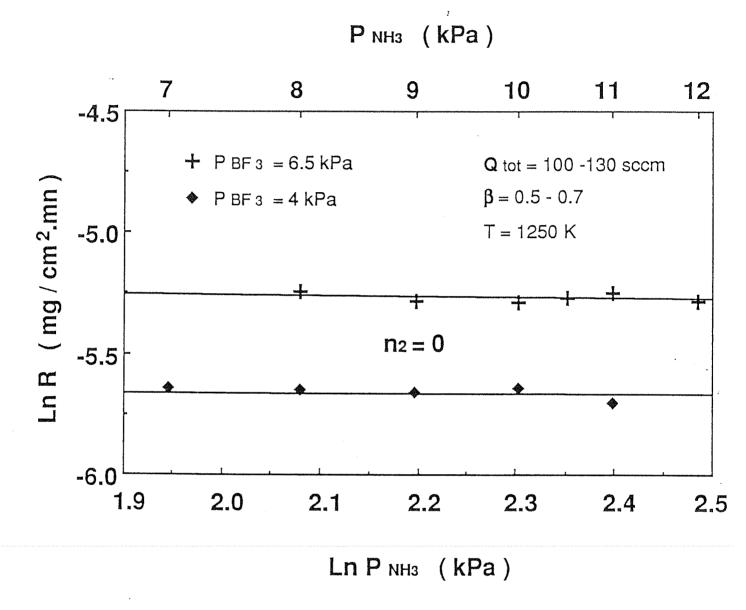


Fig.16: Variation of BN growth rate with partial pressure of NH3 for T= 1250 K

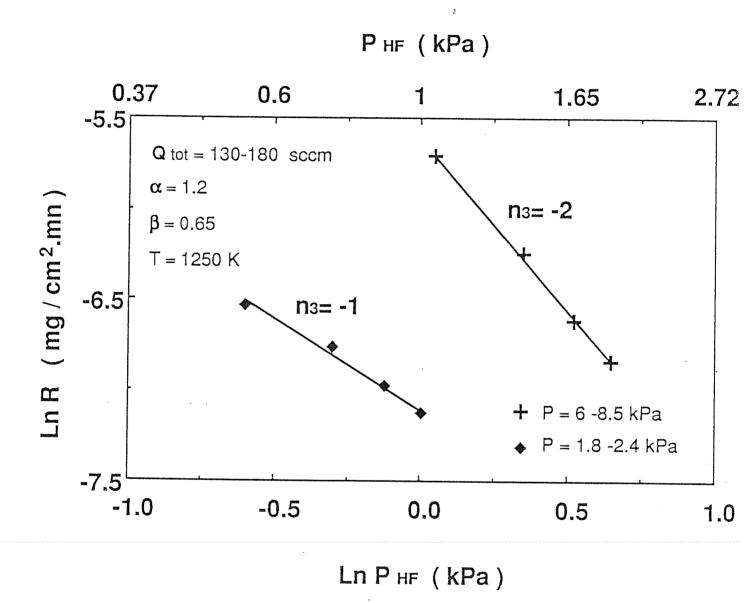


Fig.17: Variation of BN growth rate with partial pressure of HF for T= 1250 K

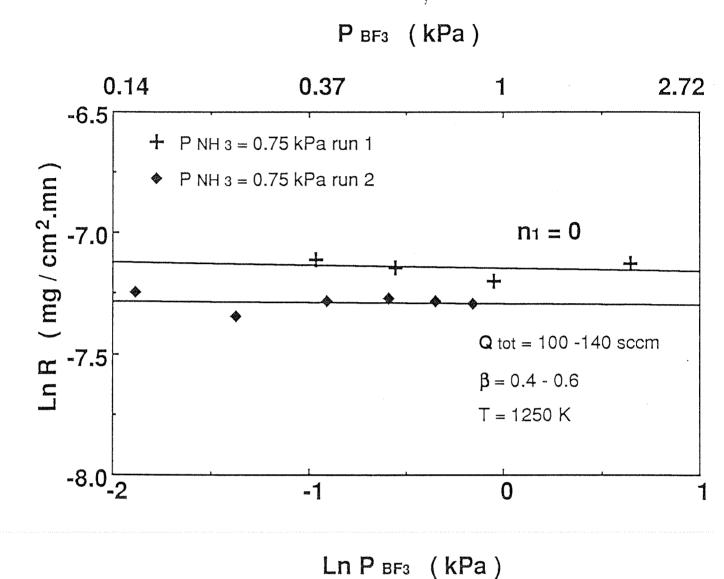


Fig.18: Variation of BN growth rate with partial pressure of BF3 for T= 1250 K

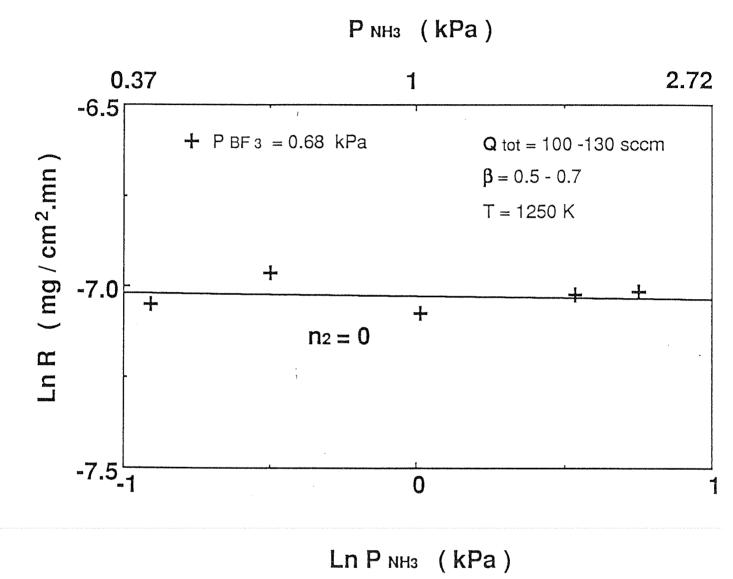


Fig.19: Variation of BN growth rate with partial pressure of NH3 for T= 1250 K

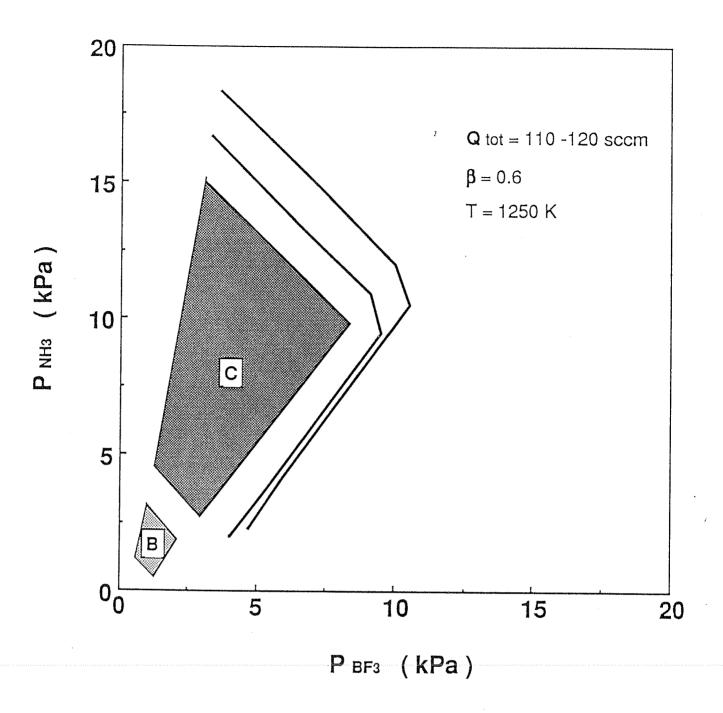


Fig.20 : Domains of validity for the kinetic laws B and C at T= 1250 K

For  $1 \le P_{tr} \le 4$  kPa and  $0.5 \le P_{HF} \le 1$  kPa  $^{7}$   $R = k_{0} \exp(-E_{a}/\Re T) [P_{BF_{3}}]^{0}$ .  $[P_{NH_{3}}]^{0}$ .  $[P_{HF}]^{-1}$ .  $[P_{Ar}]^{0}$  (Law B) where  $E_{a} = 100 \pm 20$  kJ mol<sup>-1</sup> [11],  $< k_{0} > = 9.3.10$   $^{3}$  mg.Pa/cm<sup>2</sup>.mn  $< k_{0} >$  is an average value calculated from all the experimental growth rates obtained in presence of added HF for 1250 K and  $1 \le P_{tr} \le 4$  kPa

For  $6 \le P_{tr} \le 18$  kPa,  $1.1 \le P_{HF} \le 2$  kPa  $R = k_0 \exp\left(-E_a/\Re T\right) [P_{BF_3}]^{1.5}. [P_{NH_3}]^0. [P_{HF}]^{-2}. [P_{Ar}]^0 \text{ (Law C)}$  where  $E_a = 185 \pm 15$  kJmol<sup>-1</sup> [11],  $< k_0 > = 5.4.10$  5 mg.Pa<sup>0.5</sup>/cm<sup>2</sup>.mn  $< k_0 >$  is an average value calculated from all the experimental growth rates obtained in presence of added HF for 1250 K and  $6 \le P_{tr} \le 18$  kPa

## 4- DISCUSSION

The apparent reaction order with respect to argon is zero for the three temperatures and the pressure range studied. This species has been used to prevent diffusion of corrosive gases in the microbalance. It does not participate directly to the reaction of BN formation. In the considered range of  $\beta$  ratio, Ar does not affect the kinetic process.

The deposition rate does not depend on the initial partial pressure of NH<sub>3</sub>, whatever the experimental conditions of temperature and pressure. Other authors have previously reported a similar result for two CVD systems where NH<sub>3</sub> is used as nitrogen source: BN deposited from BCl<sub>3</sub>-NH<sub>3</sub>-H<sub>2</sub> mixtures [10], and Si<sub>3</sub>N<sub>4</sub> formed from Si(CH<sub>3</sub>)<sub>4</sub>-NH<sub>3</sub>-H<sub>2</sub> mixtures [14]. A nil

apparent partial order in heterogeneous catalysis could be linked to a major adsorption of NH<sub>3</sub> or a species derived from it, e.g. the Lewis adduct BF<sub>3</sub>:NH<sub>3</sub> (identified on the cold walls of the reactor). Therefore, two different paths are considered:

Reversible adsorption: 
$$NH_3 + *_B <==> NH_3*$$
 (1)

Lewis acid-base reaction: 
$$NH_3 + BF_3 <==>BF_3:NH_3$$
 (2)  
Adduct physisorption:  $BF_3:NH_3+(*_B*_N)<=>BF_3:NH_3**$  (2')

where \* stands for an adsorption site of the substrate surface.

Although the surface electrons are somewhat delocalized, there remains an excess of electron density on  $*_N$  surface sites and a corresponding lack of electron density on the  $*_B$  sites. Consequently, any N-containing molecule adsorbs preferentially on a  $*_B$  site and any B-containing one on a  $*_N$  site, since a B--N bond is much more energetically favored than N--N or B--B bonds. This is why equation (1) involves only  $*_B$  sites and equilibrium (2') involves ( $*_B*_N$ ) site pairs.

The choice between different kinetic laws can arise from the nature of the major adsorbed species, NH<sub>3</sub> or the adduct BF<sub>3</sub>:NH<sub>3</sub>. Adduct formation (2) is known to be a rapid reaction at low temperatures [15]. Reaction (1) should be considered at higher temperatures than reactions (2)-(2').

BF<sub>3</sub> species seems to play different mechanistic rôles according to the CVD conditions, as indicated by the three different partial orders 1, 1.5, and 0. The 0 order may arise from the existence of a major adsorption effect as for NH<sub>3</sub>; in this case, equilibria (2)-(2') account for 0 order simultaneously for BF<sub>3</sub> and NH<sub>3</sub>. These equilibria are expected at low temperatures; indeed, partial order 0 is obtained for BF<sub>3</sub> at low temperatures and low pressures (law B). On

the other hand, first-order kinetics with respect to BF<sub>3</sub> are expected at higher temperatures, where equilibrium (1) is predominant. BF<sub>3</sub> can then react with the abundant NH<sub>3</sub>\* to give some intermediate adsorbed species:

- either by an Eley-Rideal (E R) mechanism:

$$NH_3^* + BF_3 \le BF_3: NH_3^*$$
 (3)

$$BF_3:NH_3 * + *_N <==> B \equiv N** + 3 HF$$
 (3')

- or by a Langmuir-Hinshelwood (L H) bimolecular mechanism:

$$BF_3 + *_N < ==> BF_3*$$
 (4)

$$BF_3^* + NH_3^* < ==> B \equiv N^{**} + 3 HF$$
 (4')

The partial order 1.5 arises probably from more complex mechanisms, involving complex intermediates such as cyclic compounds and/or competition between two or more reaction paths.

The apparent partial order relative to HF is either -3, -2, or -1 depending on the conditions. Etching is not believed to occur, because even a HF-rich gas phase composition does not lead to weight loss. Explanation of negative integer orders can lie in the number of HF molecules which must be eliminated in order to obtain some critical intermediate species.

# 4.1- Mechanism A (T > 1300 K)

In this case, the gas phase adduct formation is not important; on the other hand, NH<sub>3</sub> adsorption is predominant (Eq. (A1)). BF<sub>3</sub> reacts with it according to an E-R or L-H mechanism. Both paths result in the formation of

 $B\equiv N^{**}$  chemisorbed intermediate and elimination of 3 HF molecules (Eq. (A2)). The remaining  $B\equiv N^{**}$  adsorbed molecule is then slowly and irreversibly incorporated to the deposit network (because it probably has to migrate to a stable site (Eq. (A3)). The mechanism is summarized by the following equations:

$$NH_3 + *_B <==> NH_3*$$
 (A1)

$$BF_3 + NH_3^* + *_N \le B \equiv N^{**} + 3 HF$$
 (A2)

$$B \equiv N^{**} \longrightarrow BN + (*_B^*_N)$$
 (A3)

The final rate R derived from equation (A3):

$$R = k_3.[B \equiv N^{**}]$$

The intermediate  $[B\equiv N^{**}]$  is calculated upon the assumption of quasisteady-state regime:

steady-state regime: 
$$\frac{d[B\equiv N^{**}]}{dt} = k_2 \; P_{BF_3} \, [NH_3^*]. \\ \theta_N - \, k_{-2} \, [B\equiv N^{**} \,] \; P_{HF}^3 \, - \, k_3 \, [B\equiv N^{**}] = 0$$

$$[B = N^{**}] = \frac{k_2 P_{BF_3} [NH_3^*].\theta_N}{k_3 + k_2 P_{HF}^3}$$

where  $\theta_N$  is the fraction of  $*_N$  sites uncovered and  $[NH_3*]$  the fraction of  $*_B$  sites covered with  $NH_3$ .

If 
$$k_3 << k_{-2} P_{HF}^3$$
, then  $[B \equiv N^{**}] \approx K_2 [NH_3^*] \theta_N P_{BF_3} P_{HF}^{-3}$ , with  $K_2 = k_2 / k_{-2}$ 

Under the double assumption that  $[NH_3^*]\approx 1$  and that  $\theta_{N^*}\approx 1$  (predominant adsorption of  $NH_3$  on  $*_B$ , partial orders corresponding to those actually observed (law A) are derived from the following equation:

$$R = k_3 K_2.P_{BF_3}.P_{HF}^{-3}$$
 (Eq. 1)

In order to determine the influence of  $\alpha$  on the chemical composition of the deposits prepared under the conditions of the law A, thick films of BN were synthesized, at 1450 K and Ptr= 1.5 kPa, on flat sintered  $\alpha$ -SiC substrates and analysed by using an electron probe X-ray microanalyser (EPMA)<sup>1</sup>. The results are listed in Table 1. It was found that N/B ratios are nearly equal to the stoichiometric value when  $\alpha \geq 1$ .

On the other hand, when  $\alpha \le 1$  (i. e.  $P_{NH_3} < P_{BF_3}$  in the initial gaseous mixture), the obtained deposit contains more boron than nitrogen in atomic percentage. The apparent reaction orders have not been determined for these  $\alpha$  values, but this chemical composition suggests competition between two mechanisms, one conducting to BN, the other to boron containing species (i. e. oxides). The latter assumes a non-negligible BF<sub>3</sub> adsorption ( the major species in the gaseous phase) and a decrease of NH<sub>3</sub> adsorption, in contradiction with the hypotheses leading to the eq. 1.

# 4.2- Mechanism B (T $\leq$ 1300 K; 1 $\leq$ P<sub>tr</sub> $\leq$ 4 kPa)

In this case, and as suggested by the partial nil orders with respect to NH<sub>3</sub> and BF<sub>3</sub>, the BF<sub>3</sub>:NH<sub>3</sub> adduct exists in the gas phase (Eq. (B1)) and physisorbs majoritarily on the substrate following (2') (Eq. (B2)). An intermediate stage is the formation of a chemisorbed species BF<sub>2</sub>-NH<sub>2</sub> by elimination of one HF molecule (Eq. (B3)). This intermediate species is then irreversibly incorporated to the substrate, eliminating slowly and irreversibly

<sup>&</sup>lt;sup>1</sup> 75 fromCAMEBAX

| α   | B ( % at. )                      | N ( % at. ) | O ( % at. )                     | N / B ( at. )                     |
|-----|----------------------------------|-------------|---------------------------------|-----------------------------------|
| 0.5 | 48.4 ± 0.5                       | 42.1 ± 1.4  | 9.2 ± 1                         | 0.87 ± 0.05                       |
| 0.7 | 47.7 ± 0.6                       | 42.7 ± 0.5  | $\textbf{8.4} \pm \textbf{0.4}$ | $\textbf{0.89} \pm \textbf{0.03}$ |
| 1   | $\textbf{48.0} \pm \textbf{0.7}$ | 42.4 ± 0.5  | 9 ± 0.2                         | $\textbf{0.88} \pm \textbf{0.03}$ |
| 1.2 | $46.4 \pm 0.5$                   | 44.0 ± 0.3  | 8.9 ± 0.3                       | 0.95 ± 0.02                       |
| 2   | $45.3\pm0.5$                     | 44.8 ± 0.5  | 9.3 ± 0.3                       | 0,99 ± 0.02                       |
| 5   | 44.4 ± 0.4                       | 43.6 ± 0.7  | 11.8 ± 0.7                      | 0.98 ± 0.02                       |

Table 1 : EPMA derived atomic compositions of the deposits for T= 1450 K, Ptr= 1.5 kPa, Qtot= 119 sccm and  $\beta$ = 0.6

two more HF molecules (Eq. (B4)). The mechanism is summarized by the following equations:

$$NH_3 + BF_3 \le BF_3: NH_3$$
 (B1)

$$BF_3:NH_3 + (*_B*_N) <==> BF_3:NH_3 **$$
 (B2)

$$BF_3:NH_3 ** <==> BF_2-NH_2** + HF$$
 (B3)

$$BF_2-NH_2 ** --->BN + 2HF + (*_B*_N)$$
 (B4)

The final rate R is expressed from reaction (B4) as:

$$R = k'_4.[BF_2-NH_2 **]$$

The intermediate  $[BF_2-NH_2\ **]$  is derived upon the assumption of quasi-steady-state regime:

$$\frac{d[BF_2\text{-}NH_2^{**}]}{dt} = k'_3 [BF_3\text{:}NH_3^{**}] - k'_{-3} [BF_2\text{-}NH_2^{**}] P_{HF} - k'_4 . [BF_2\text{-}NH_2^{**}] = 0$$

$$[BF_2\text{-}NH_2^{**}] = \frac{k'_3 [BF_3\text{:}NH_3^{**}]}{k'_4 + k'_{-3}P_{HF}}$$

If  $k'_4 \ll k'_{-3} P_{HF}$ , then  $[BF_2-NH_2 **] \approx K'_3 [BF_3:NH_3 **] P_{HF}^{-1}$ ,

with  $K'_3 = k'_3 / k'_{-3}$ 

From equation (B2), [BF3:NH3\*\*] is determined as:

$$[{\rm BF_3:}{\rm NH_3**}] = {\rm K'_2.P_{BF_3:}}{\rm NH_3}\;\theta_{\rm BN}$$

where  $\theta_{BN}$  represents the fraction of pairs of sites  $({^*\!B}^*{_N}$  ) uncovered and obeys the balance equation:

$$\theta_{\rm BN}=1\text{-}[{\rm BF_3:}{\rm NH_3**}]$$

with  $[\mathrm{BF_3:NH_3^{**}}]$  representing the fraction of pairs of sites  $(^*\mathrm{_B^*N})$  covered by the adduct.

From the two preceding equations, [BF3:NH3\*\*] is calculated to be :  $[BF_3:NH_3^{**}] = \frac{K'_2.P_{BF_3:NH_3}}{1+K'_2.P_{BF_3:NH_3}}$ 

$$[BF_3:NH_3^{**}] = \frac{K'_2.P_{BF_3:NH_3}}{1 + K'_2.P_{BF_3:NH_3}}$$

Involving the equilibrium (B1), another expression is derived:

$$[BF_3:NH_3^{**}] = \frac{K'_2.K'_1.P_{NH_3}P_{BF_3}}{1 + K'_2.K'_1P_{NH_3}P_{BF_3}}$$

The adduct presence at the surface becomes independent of  $P_{\mathrm{BF}_3}$  and  $P_{\mathrm{NH}_3}$ when K'2.K'1.P<sub>NH3</sub>P<sub>BF3</sub>>> 1. Partial orders corresponding to those observed experimentally (law B) are thus obtained, as shown by the following theoritical kinetic law:

$$R \approx k'_4.K'_3.P_{HF}^{-1}$$
 (Eq.2)

The experiment data show that the activation energy is three times smaller in this case than in mechanism A, due possibly to the lower physisorption energy of the adduct involved here with respect to that corresponding to the chemisorption of NH3 and BF3.

The above mechanism is consistent with: (i) the stoichiometry of the deposits actually observed for T= 1250 K and Ptr= 1.5 kPa, and (ii) the reaction order with respect to  $\mathrm{BF}_3$  constant and equal to zero, whatever the values of  $\alpha$ (Table 2).

# 4.3- Mechanism C ( $T \le 1300 \text{ K}, 6 \le P_{tr} \le 18 \text{ kPa}$ )

The noninteger partial order in BF3 suggests the existence of more complex or intricate reaction paths. The adsorption of a majoritary NH3-

| α   | B ( % at. ) | N (% at.)  | O ( % at. )                     | N / B ( at. ) |
|-----|-------------|------------|---------------------------------|---------------|
| 0.5 | 46.7 ± 1    | 48.0 ± 1.4 | 5.3 ± 1                         | 1.03 ± 0.05   |
| 0.7 | 48.1 ± 0.8  | 49.4 ± 0.6 | 2.4 ± 0.3                       | 1.03 ± 0.03   |
| 1   | 46.3 ± 1.9  | 48.2 ± 1.8 | $\textbf{4.5} \pm \textbf{0.3}$ | 1.04 ± 0.07   |
| 1.2 | 45.7 ± 1.6  | 48.5 ± 1.5 | 4.4± 0.5                        | 1.05 ± 0.05   |
| 2   | 46.7 ± 0.3  | 49.3 ± 0.2 | 3.0 ± 0.1                       | 1.05 ± 0.01   |
| 5   | 47.3 ± 1.8  | 49.5 ± 1.5 | 3.4 ± 0.3                       | 1.04 ± 0.06   |

Table 2 : EPMA derived atomic compositions of the deposits for T= 1250 K, Ptr= 1.5 kPa, Qtot= 119 sccm and  $\beta$ = 0.6

containing species at the surface should be valid (NH<sub>3</sub> partial order is 0). Nevertheless, no complete set of equations could be properly written yet.

## 5- CONCLUSION

The present experimental kinetic study of the CVD of BN from  $BF_3$ - $NH_3$ -Ar mixtures establishes the influence of the initial gas phase composition on the transition from mass transer to chemical reaction rate-controlled processes for three temperatures. The latter domain (in terms of  $P_{NH_3}$ ,  $P_{BF_3}$ ) is significantly narrowed when (i)  $BF_3$  becomes the major reactive species, and (ii) the temperature is increased.

In the chemical rate-controlled regime, three distinct experimental kinetic laws have been written (when  $\alpha > 1$ ) as:

## Law A

$$\begin{split} R &= k_0 \; exp \; (-E_a/\Re T) \; [P_{BF_3} \;]^1. \; [P_{NH_3}]^0. \; [P_{HF}]^{-3}. \; [P_{Ar}]^0 \\ &= k_0 > = 1.03.10 \; 14 \; mg. Pa^2/cm^2.mn, \; for \; T=1450 \; K \; and \; P_{tr} \leq 4 \; kPa \\ &< k_0 > = 6.5.10 \; 14 \; mg. Pa^2/cm^2.mn, \; for \; T=1350 \; K \; and \; P_{tr} \leq 9 \; kPa \end{split}$$

## Law B

$$\begin{split} R &= k_0 \; exp \; (-E_a/\Re T) \; [P_{BF_3}]^0. \; [P_{NH_3}]^0. \; [P_{HF}]^{-1}. \; [P_{Ar}]^0 \quad (Law \; B) \\ where \; E_a &= 100 \pm 20 \; kJ \; mole^{-1} \; and < k_0 > = 9.3.10 \; 3 \; mg. Pa/cm^2.mn \\ for \; T &= 1250 \; K \; and \; 1 \leq P_{tr} \leq 4 \; kPa \end{split}$$

#### Law C

$$\begin{split} R &= k_0 \; exp \; (-E_a/RT) \; [P_{BF_3} \;]^{1.5}. \; [P_{NH_3}]^0. \; [P_{HF}]^{-2}. \; [P_{Ar}]^0 \; \; (Law \; C) \\ where \; E_a &= 185 \pm 15 \; kJ mole^{-1} \; and < k_0 > = 5.4.10 \; ^3 \; mg. Pa^{0.5}/cm^2.mn \\ for \; T &= 1250 \; K \; and \; 6 \leq P_{tr} \leq 18 \; kPa \end{split}$$

Two mechanisms, accounting for these kinetic laws, are proposed to explain the chemical deposition processes of BN; one corresponding to law A and the second to law B. The former is based on the hypothesis of a predominant NH<sub>3</sub> adsorption, the adsorbed species reacting with BF<sub>3</sub> according to Eley-Rideal or Langmuir-Hinshelwood mechanisms with the simultaneous evolution of three HF molecules. The latter assumes the occurrence of the BF<sub>3</sub>:NH<sub>3</sub> adduct in the gas phase, its physisorption on the solid and the evolution of three HF molecules in two steps.

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## REFERENCES

[1]- T. KIMURA, K. YAMOMOTO, T. SHIMIZU and S. YUGO, Thin Solid Films, 70 (1980) 351-362

- [2]- K. NAKAMURA, J. Electrochem. Soc., 133, 6 (1986) 1120-1123
- [3]- S. MOTOJIMA, Y. TAMURA and K. SUGIYAMA, Thin Solid Films, 88 (1982) 269-274
- [4]- T. TAKAHASHI, H. ITOH and A. TAKEUCHI, J. Crystal Growth, 47, (1979) 245-250
- [5]- T. MATSUDA, N. UNO, H. NAKAE and T. HIRAI, J. Mater. Sci., 21 (1986)649-658
- [6]- T. MATSUDA, H. NAKAE and T. HIRAI, J. Mater. Sci., 23 (1988) 509-514
- [7]- A. W. MOORE, S. L. STRONG, Ceram Eng. Proc., 10 [7-8] (1989) 846-856
- [8]- T. MATSUDA, J. Mater. Sci., 24 (1988) 2353-2358
- [9]- A. MARCHAND, G. LACRAMBE and M TRINQUECOSTE, Carbon, 18, 23 (1988) 355-357
- [10]- H. TANJI, K. MONDEN and M. IDE, Proc. 10th Int. Conf. on CVD, G.W. Cullen, ed., The Electrochem. Soc., Pennington (1987) 562-569
- [11]- S. PROUHET, F. LANGLAIS, A. GUETTE and R. NASLAIN submitted to European J. of Solid State and Inorg. Chem.

[12]- H. TANAKA, N. NAKANISHI and E. KATO, Proc. 10th Int. Conf. on CVD, G.W. Cullen, ed., The Electrochem. Soc., Pennington (1987) 155-164

[13]- K.S. YI and J.S. CHUN, Proc. 10th Int. Conf. on CVD, G.W. Cullen, ed., The Electrochem. Soc., Pennington (1987) 570-578

[14]- N. ROELS, T. LECOINTE, R. CUINEBRETIERE and J. DESMAISON, J. de Physique, Colloque C5, suppl. to n° 5, **50** (1989) 435-444

[15] A.W. LAUGENBAYER, G.F. CONDIKE, J.Am.Chem.Soc., 70, (1948) 2274

## **APPENDIX**

The figure A1 represents a plane  $(P_{BF_3}, P_{NH_3})$  consituted where the coordinates of a given point are related to  $\alpha$  and  $P_{tr}$  according to the following transformation:

$$P_{NH_3} = \frac{\alpha}{1+\alpha} P_{tr}$$

$$P_{BF_3} = \frac{1}{1+\alpha} P_{tr}$$

This transformation is merely the inverse expression of  $\alpha$  and  $P_{tr}$  as functions of  $P_{NH_3}$  and  $P_{BF_3}$ . Any point M of coordinates (  $P_{BF_3}$ ,  $P_{NH_3}$ ) is characterized by a total reactive pressure equal to the sum of its coordinates (  $P_{tr} = P_{BF_3} + P_{NH_3}$ ). The  $\alpha$  value is given by their ratio (  $\alpha = P_{NH_3}/P_{BF_3}$ ). All the points corresponding to the same total reactive pressure (  $P_{tr}$ ) build up a segment, between  $M_1$  (  $P_{tr}$ ,0) and  $M_2$  (0,P\_{tr}). A shift towards  $M_2$  along this segment increases the  $\alpha$  ratio. Similarly, the points corresponding to a constant  $\alpha$  ratio form a straight line joining the origin O and M. Along this line, the total reactive pressure increases by moving away from the origin. Varying the partial pressure of one of the reactive species (  $P_{BF_3}$  or  $P_{NH_3}$  ) corresponds to moving along a segment parallel to the appropriate axis.

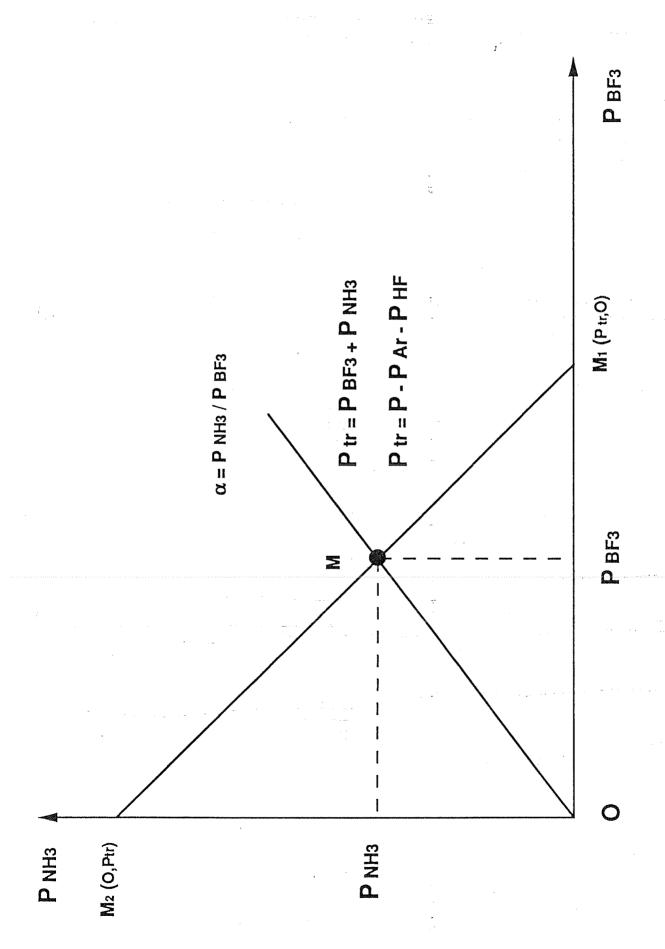


Fig.A1 : Signification of  $\alpha$  and  $P_{tr}$  in the plane (P BF3,P NH3)